

AMENDMENTS TO THE ABSTRACT OF THE DISCLOSURE:

Kindly replace the Abstract of the Disclosure with the following new Abstract:

The present invention ~~is for supplying~~ supplies a specified quantity Q of processing gas while dividing at a desired flow rate ratio $Q1/Q2$ accurately and quickly from a gas supply facility equipped with a flow controller into a chamber. ~~With the present invention,~~ a total quantity $Q=Q1+Q2$ of gas while dividing is supplied into a chamber C at a desired flow rate $Q1$ and $Q2$ through shower plates ~~3 and 4~~ fixed to the ends of branch supply lines ~~GL1 and GL2~~ by providing open/close valves ~~OV1 and OV2~~ with a plurality of branch supply lines $GL1$ and $GL2$, respectively, to supply the specified quantity Q of gas G from the gas supply facility ~~equipped with a flow controller QCS~~ into a chamber, and by utilizing a bypass line $BL1$ on the downstream side of the ~~above-mentioned~~ open/close valve $OV1$ and branched from $GL1$, a bypass line $BL2$ on the downstream side of the open/close valve $OV2$ and branched from $GL2$, a pressure type division quantity controller ~~FV~~ connected to the bypass line $BL1$ and the bypass line $BL2$, a ~~pressure sensor PS1~~ to measuring pressure inside the branch supply line $GL1$, and ~~another pressure sensor PS2~~ to measuring pressure inside the branch supply line $GL2$.